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Electrical and optical properties of CZTS thin films prepared by SILAR method

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ABSTRACT

In the present work, Cu_2ZnSnS_4 (CZTS) thin film was deposited onto the glass substrate by simple and economic SILAR method and its structural, morphological, optical and electrical properties were analyzed. X-ray diffraction (XRD) analysis confirms the formation of CZTS with kesterite structure and the average crystallite size is found to be 142 nm. Scanning electron microscope (SEM) image shows that the film has homogeneous, agglomerated surface without any cracks. The prepared CZTS film shows good optical absorption (10^4 cm^{-1}) in the visible region and the optical band gap energy is found to be quite close to the optimum value of about 1.54 eV for solar cell application. The refractive index of the prepared film is found to be 2.85. The electrical resistivity of the film is found to be $\sim 10^{-2}$ Ω cm at room temperature.

1. Introduction

Optical property of thin films found a large number of disparate applications in science and technology coatings [1]. Cu_2ZnSnS_4 (CZTS) film has gained much interest in recent years, due to the fact that its optical property is optimum (1.4–1.5 eV) for photovoltaic application [2]. CZTS is a p-type semiconductor which has an optimum band gap, and large absorption coefficient (>10^4 cm^{-1}) makes it an alternate potential candidate for thin film solar cells [3].

Recently, Noriko Moritake et al. have reported the fabrication of CZTS thin film solar cells by the sol–gel method by the sulfurizing of precursors. The structure of the solar cells was Al/ZnO:Al/CdS/CZTS/Mo/Soda Lime Glass substrate and the Power Conversion Efficiency (PCE) of the cell was 1.61% [4]. Sudip K. Saha et al. prepared CZTS-fullerene hybrid p–n junction solar cells by hot injection method and have reported 0.9% PCE [5]. Jin Woo Cho et al. reported the PCE of 3.02% for spin coated CZTS thin films [6]. Subramaniam et al. have reported 1.34% PCE for CZTS film deposited by chemical bath deposition method [2]. Suryawansi et al. prepared CZTS by SILAR method and obtained PCE of about 3.81% [7]. The reported experimental studies have shown that the PCE of CZTS film varies considerably by preparation methods such as RF sputtering [8], electron beam evaporation [9], thermal evaporation [10], spray pyrolysis [11], spin coating [12], pulsed laser deposition [13], electrodeposition process [14] and SILAR method [15]. The main drawback of these methods is that they require sulfurization for CZTS film formation, in which either N_2 or H_2S atmosphere is required for annealing [7]. To overcome the drawback, Successive Ionic Layer Adsorption and Reaction (SILAR) method is the preferable one which is very simple, cheap and suitable for making uniform and large area thin films. This SILAR method is relatively a new and less investigated method. In addition, this method is also suitable for metal sulfide, selenides, tellurides and oxides [16–18]. In this method, thin films are obtained by immersing the substrate directly into anionic and cationic precursors and rinsing between every immersion with distilled water. On the other hand, literature survey shows that there are only a few reports [7,15–17] available on the synthesis of CZTS thin film using SILAR route. The authors have studied its structural, optical and PEC studies of the SILAR deposited CZTS thin films. Hence, the objective of the work is to deposit CZTS thin film on transparent glass substrate and to study its structural, optical and electrical properties.

2. Experimental

In this study CZTS thin film was deposited on glass substrate using SILAR method at room temperature. A.R. grade of $CuSO_4$,

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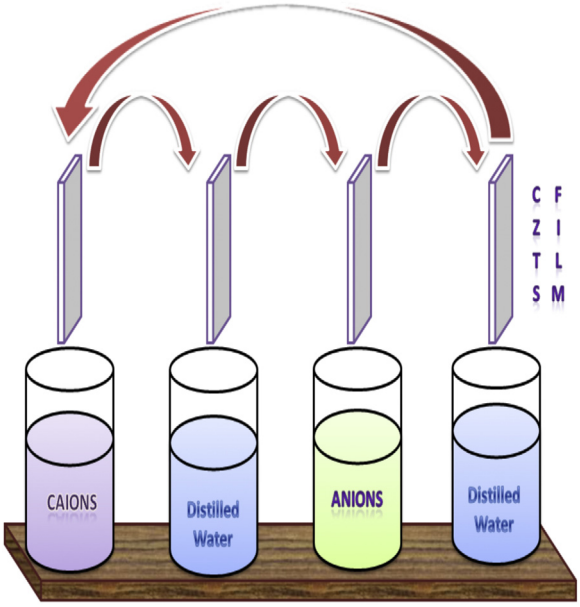

Fig. 1. Schematic representation of CZTS thin film deposited by SILAR method.

$ZnSO_4$, $SnCl_2$ and Na_2S precursor were used without any modification. Substrate cleaning plays an important role in the preparation of thin films and the cleaning process was adopted according to the earlier report [19].

The experimental process consists of four beakers: the first beaker contains mixed cationic precursor solution (40 ml) of 0.1 M $CuSO_4$, 0.05 M $ZnSO_4$ and 0.05 M $SnCl_2$, the second beaker has sufficient amount of distilled water to remove loosely adsorbed cations from the substrate, the third beaker consists of 0.2 M Na_2S anionic precursor solution and the fourth beaker contains double distilled water to remove the powdery deposit or precipitate on the substrate. In this method, the growth kinetics of a thin film deposition process involves ion-by-ion deposition at nucleation sites on the immersed surfaces.

In typical deposition, substrates were immersed separately in cation and anion precursor solution with simultaneous rinsing by using distilled water between every immersion to avoid any precipitation. First the ultrasonically cleaned substrate was immersed vertically into the cationic precursor solution for 30 s in which cations ions are adsorbed on the glass substrate. Consequently the substrate rinsed with distilled water for 10 s to remove the loosely bonded ions was again immersed into the anionic precursor solution for 30 s where the anions react with the pre-adsorbed cations to form CZTS layer on a glass substrate and finally rinsed with distilled water for 10 s to remove the unreacted cation ions, anions and loosely bonded powdery CZTS particles. The above four steps (Fig. 1) form one SILAR cycle. Similarly, 70 SILAR cycles were made to deposit CZTS thin film. The deposited films were annealed at 250 °C for 2 h in air atmosphere.

The film thickness was determined by using the standard procedure [20] and it is found to be 177 nm. The structural characteristics of films were characterized by using Cu Kα (PANalytical X'Pert Pro Powder diffractometer) monochromatic radiation source (λ = 1.5406 Å) in the range of $2\theta = 10°–80°$. The surface morphology of the film was recorded using scanning electron microscope (JEOL SEM model JEM-5610 LV). Optical absorption spectrum was recorded using JASCO UVIDEC – 650 UV–Vis spectrophotometer and electrical property of the film was measured by using AUT85670 setup.

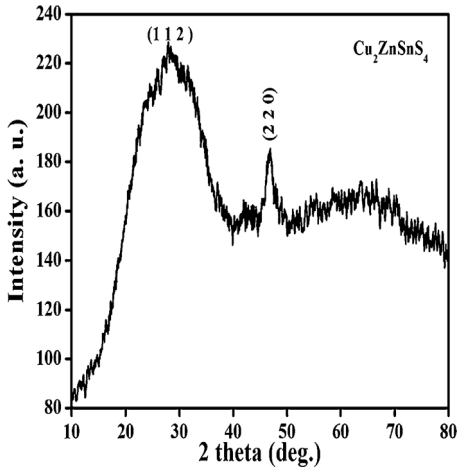

Fig. 2. XRD pattern of CZTS thin film.

3. Results and discussion

Fig. 2 shows the XRD pattern of CZTS thin film that indicates characteristic peak (2 2 0) and (1 1 2) corresponding to kesterite structure [JCPDS card no. 26-0575]. Similarly R. Lydia and P. Sreedhara Reddy prepared CZTS nanoparticles with a major peak along (2 2 0) by co-precipitation [21]. The wide peak from $2\theta = 10–30°$ may be attributed to the glass substrate.

The crystallite size was estimated by using Scherrer's formula [15]

$$D = \frac{0.9\lambda}{\beta \cos\theta} \quad (1)$$

where β is full width at half maximum (FWHM), λ is the wavelength of X-ray source, θ is the Bragg's angle. The prepared CZTS film is polycrystalline in nature, and hence large number of grains with various relative positions and orientations cause variations in the phase difference between the wave scattered by one grain and the others. The total intensity scattered by all grains is the sum of individual intensities scattered by each grain [22]. On the other hand, the stresses are one of the most important unfavorable factors affecting the structural properties that can result from geometric mismatch at boundaries between crystalline lattices of films and substrate [23]. These stresses can cause microstrains (e) in the films.

The microstrain can be calculated from the following relation [24]

$$\varepsilon = \frac{\beta \cos\theta}{4} \quad (2)$$

A dislocation is an imperfection in a crystal associated with the misregistry of the lattice in one part of the crystal with that in another part. Unlike vacancies and interstitial atoms, dislocations are not equilibrium imperfections [25]. The regular patterns are interrupted by dislocations or crystallographic defects [26].

The dislocation density (δ) was evaluated by the formula [21]

$$\delta = \frac{1}{D^2} \quad (3)$$

The stacking fault probability α is the fraction of layers undergoing stacking sequence faults in a given crystal and hence one fault is expected to be found in $1/\alpha$ layers. The presence of stacking faults gives rise to a shift in the peak positions of different reflections with respect to ideal positions of a fault-free well-annealed sample [27]. The stacking fault probabilities were calculated from the shift of the X-ray line of the film with reference (JCPDS database No: 26-0575),